

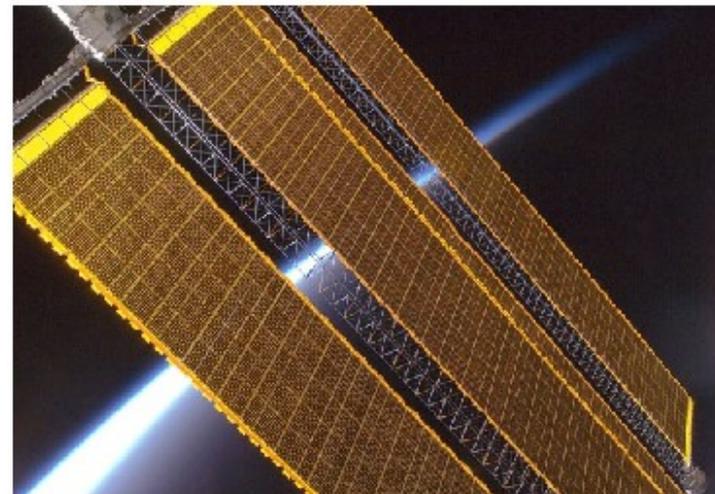
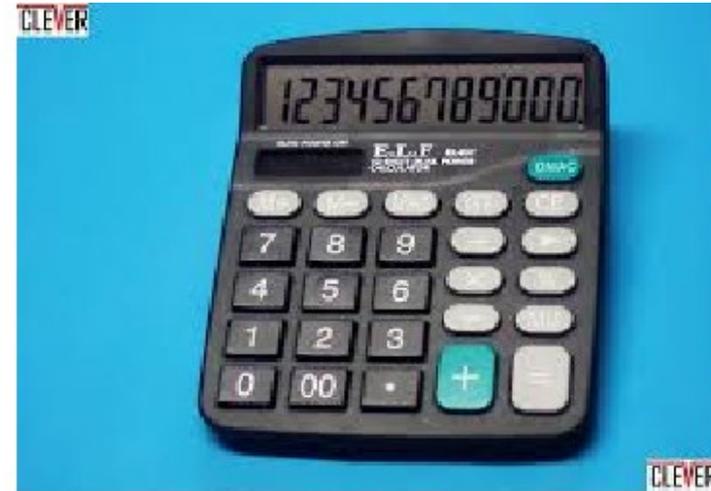
**LAMMPS User Group Meeting
August 7-8, 2013**

**PECVD generated Silicon films with
kinetic Monte Carlo and LAMMPS
molecular dynamics**

Dr. Andreas Bick



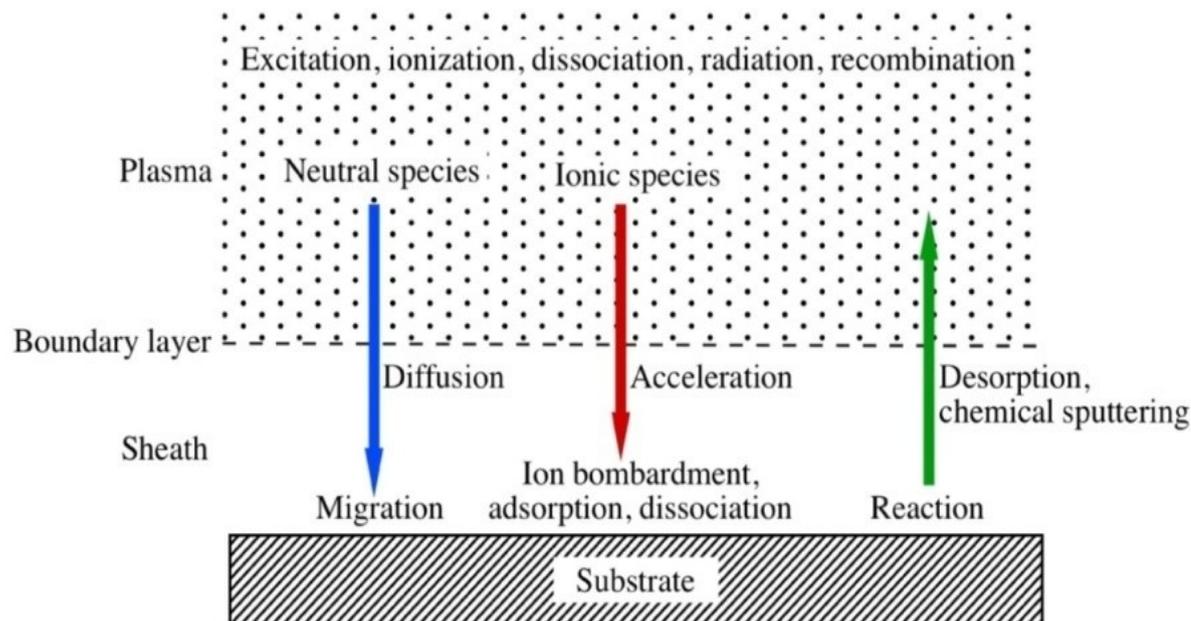
Motivation: Silicon is everywhere



Plasma Enhanced Vapor Deposition

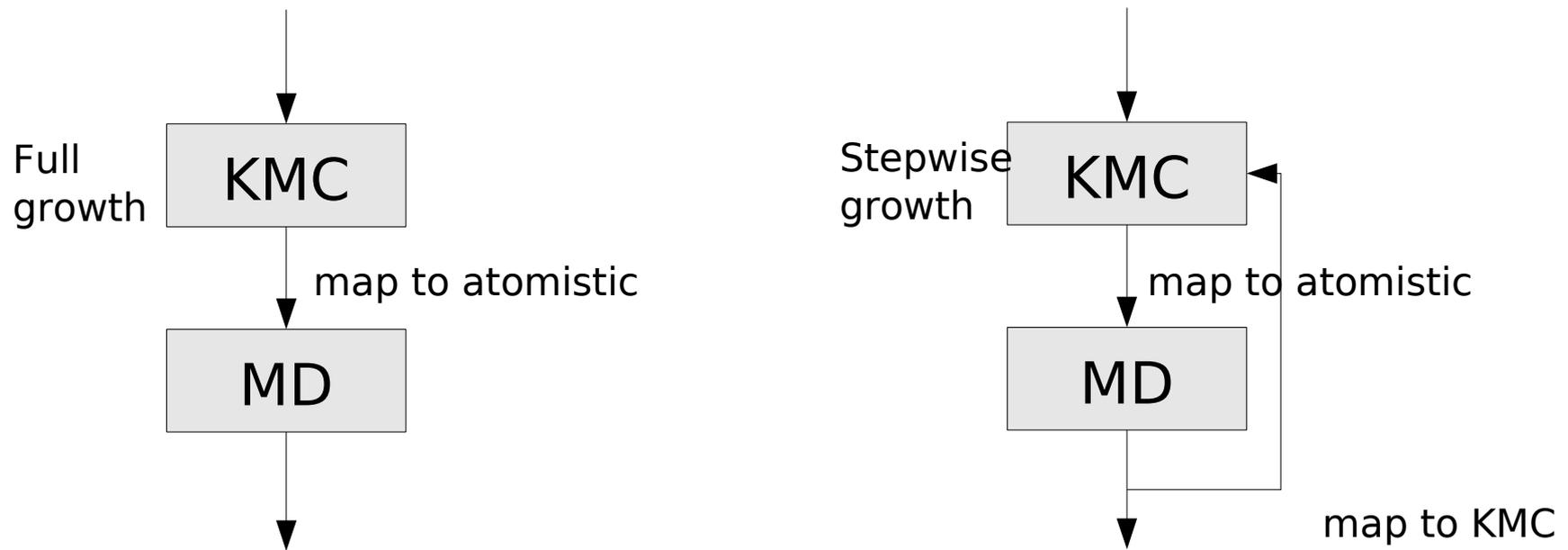
■ Chemical Reaction

- $\text{SiH}_4 \rightarrow \text{Si} + 2 \text{H}_2$
- Deposits thin films from a gas state (vapor) to a solid state on a substrate
- Used for electronics, optoelectronics and photovoltaic applications
- Fast deposition at low temperatures
- Surface interactions and film growth not yet fully understood



Combine KMC and MD

Experiment conditions



Film properties

Kinetic Monte Carlo(n- fold method)

- **Based on Diamond lattice**
- **Complex chemical reaction involving different radical species**
 - Physisorptions & Chemisorptions of gas phase radicals
 - Bulkilization of Hydrogen passivated Si
 - Subsequent abstraction of surface atoms (Eley-Rideal Hydrogen Abstractions)
 - Surface diffusion of physisorbed radicals
- **Two separate reaction steps (Decoupled diffusion methodology)**
 - Diffusion (Markovian Random Walk)
 - All the other reactions

Kinetic Monte Carlo(n- fold method) II

- At each step a complete list of possible reactions for all surface sites is considered
- Reaction event j is randomly selected according to:

$$R = \sum_{i=1}^{i=M} r_i \quad \frac{\sum_{i=1}^{i=j-1} r_i}{R} < \xi_1 < \frac{\sum_{i=1}^{i=j} r_i}{R} \quad (1)$$

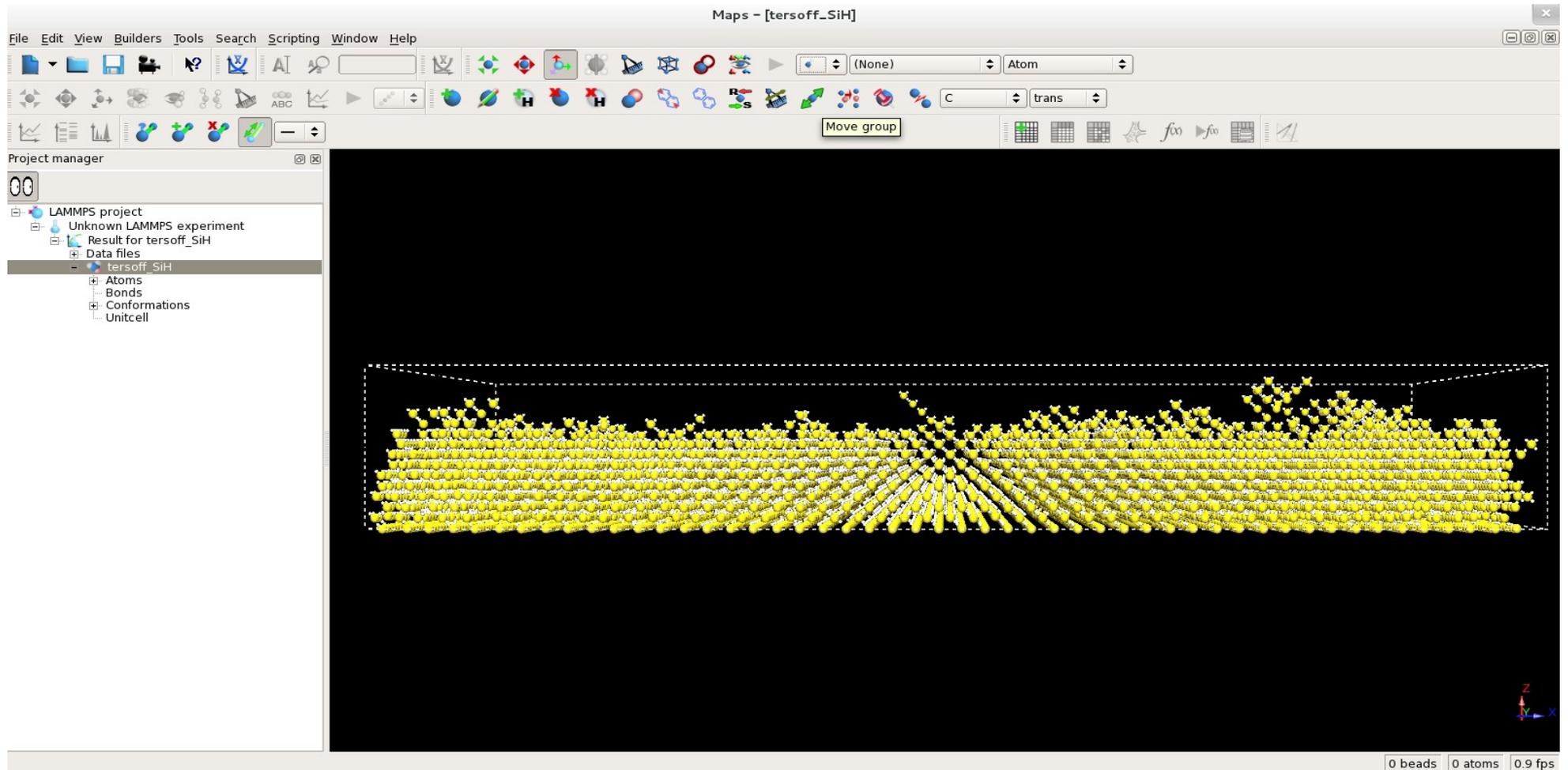
with the random number χ , the total number of possible reactions per step M and the reaction rate r

- The time increment δt is calculated as

$$\delta t = -\frac{\ln(\xi_2)}{R} \quad (2)$$

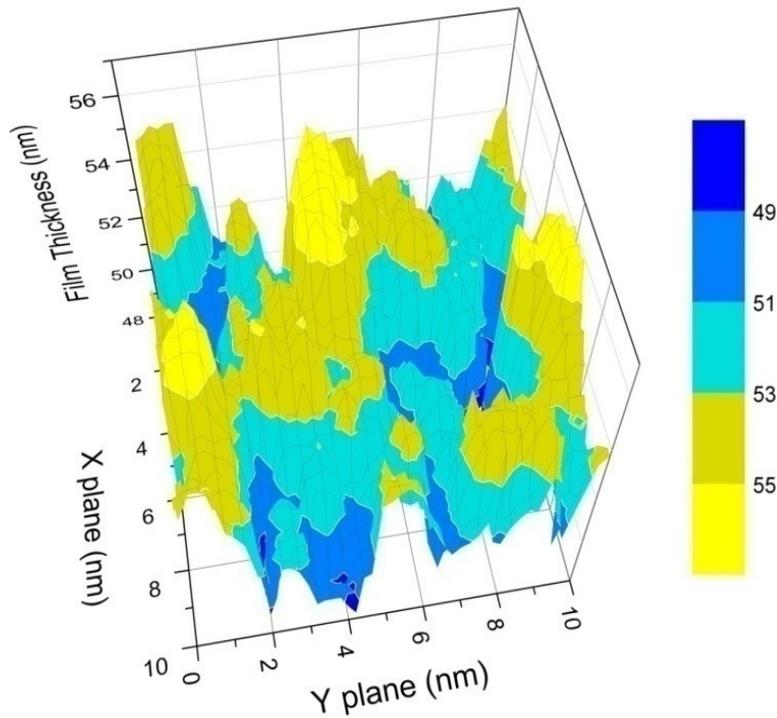
KMC Results:

■ Snapshot of KMC generated surface visualized in MAPS:

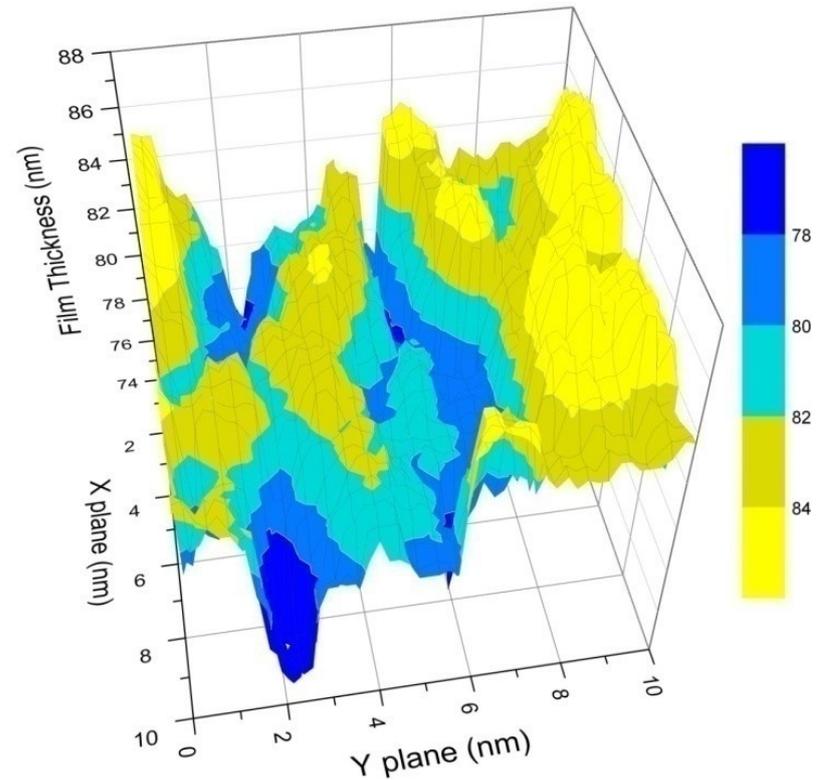


KMC Results:

- Surface thickness dependent on SiH content:

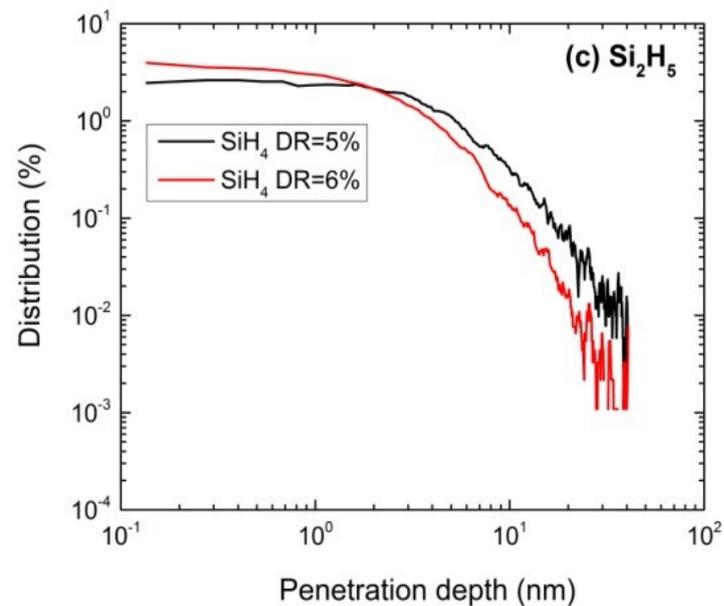
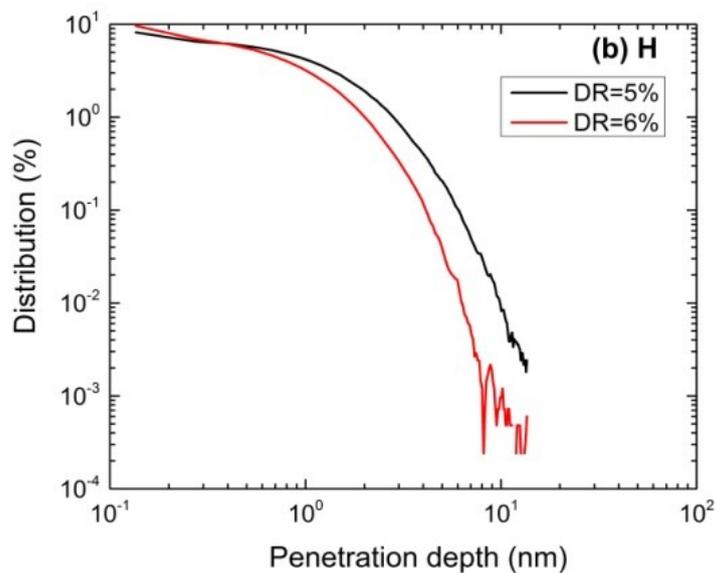
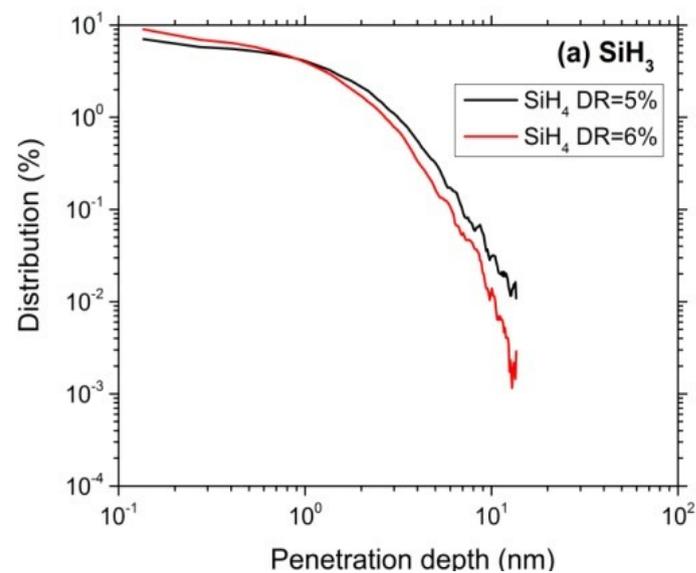
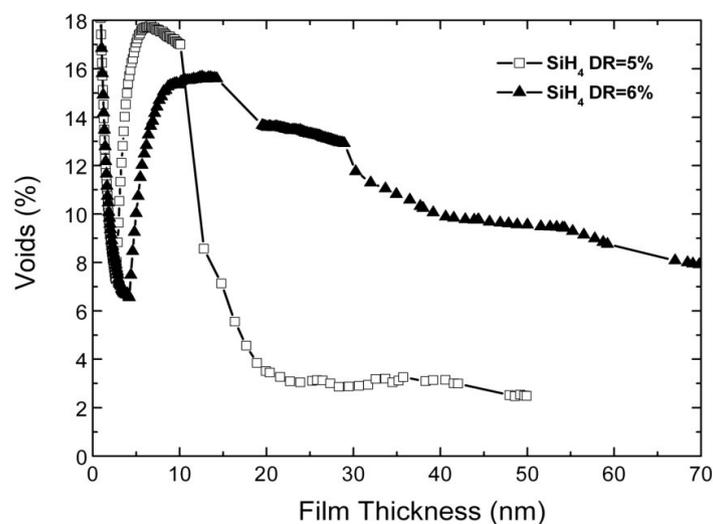


5 % SiH



6 % SiH

KMC Results: Void distribution



Molecular Dynamics (LAMMPS)

- Newton's equation of motion

$$F = m a$$

- The force can be written as the gradient of the potential energy

$$F = -\nabla V$$

- Combine the two equations to get

$$\frac{dV}{dr} = -m \frac{d^2 r}{dt^2}$$

- A trajectory is obtained by solving this differential equation
- NVT Simulations using the Nose Hoover thermostat at 180 K performed for this study

Tersoff Potential

- **Bond Order Potential**
- **Strength of a chemical bond depends on the bonding environment, including the number of bonds and possibly also angles and bond length**
- **Exists in several modifications**
- **Implementation in LAMMPS needed modification to the functional form developed by Ohira**

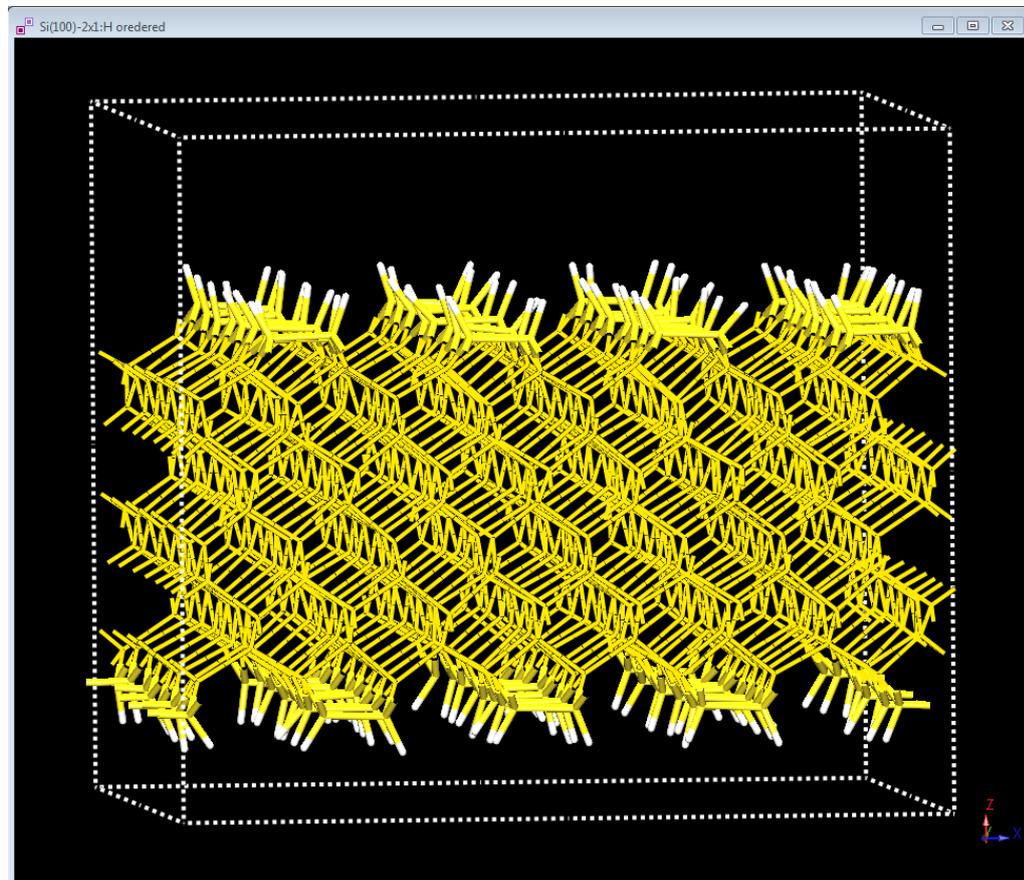
$$V_{ij} = f_C(r_{ij}) \left[a_{ij} f_R(r_{ij}) + b_{ij} f_A(r_{ij}) \right]$$

Where the interaction parameter a_{ij} describes the repulsive Si-H interaction

- **Implemented in LAMMPS for this project by Scienomics**

Tersoff Potential Validation

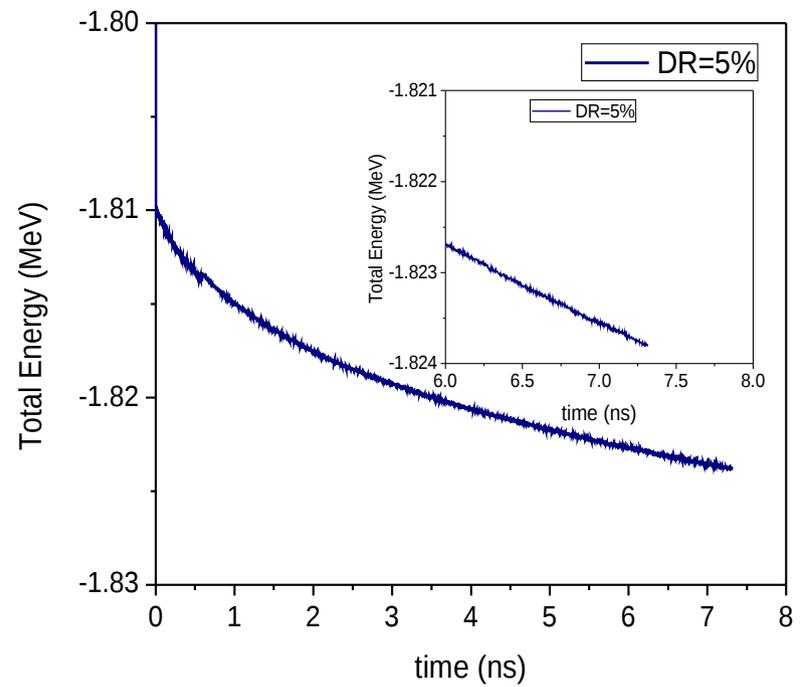
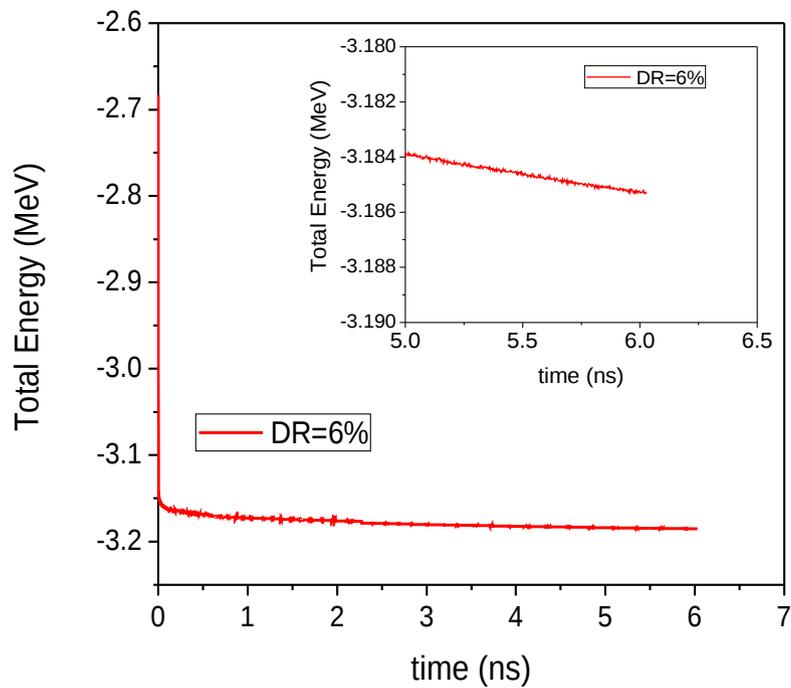
- Reproducing structural characteristics:
 - Si(100)-2x1 reconstruction
 - Si(100)-2x1 reconstructed, H terminated
 - Si-Si : 2.4 Å
 - Si-H : 1.521 Å
 - Si-Si-H : 111.9 deg



Ohira et al, *Phys. Rev. B*, 52, 8283, 1995
Ohira et al, *Surface Science*, 458, 216-228, 2000

LAMMPS MD Results:

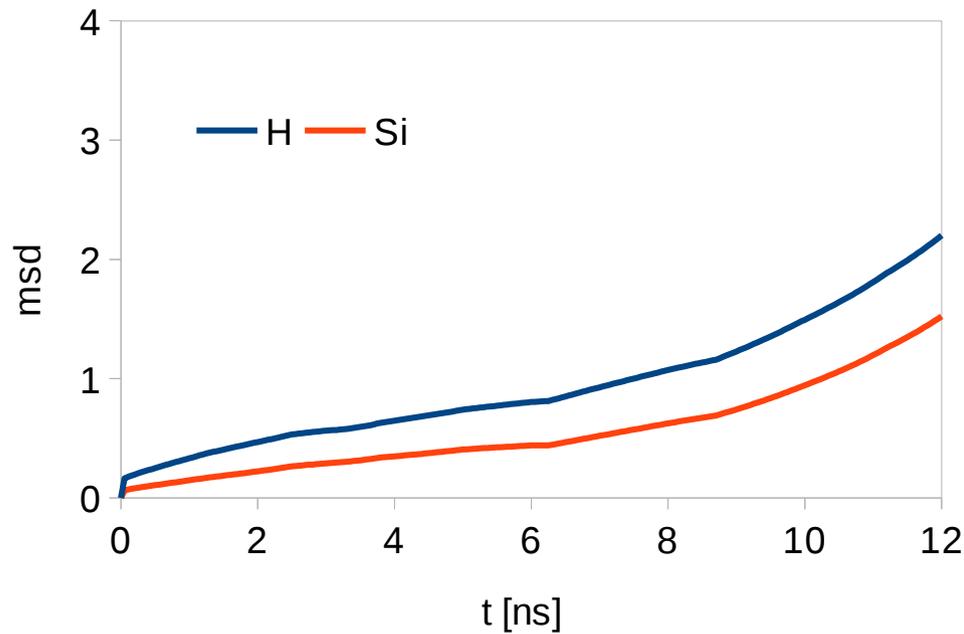
■ Convergence of total energy:



LAMMPS MD Results:

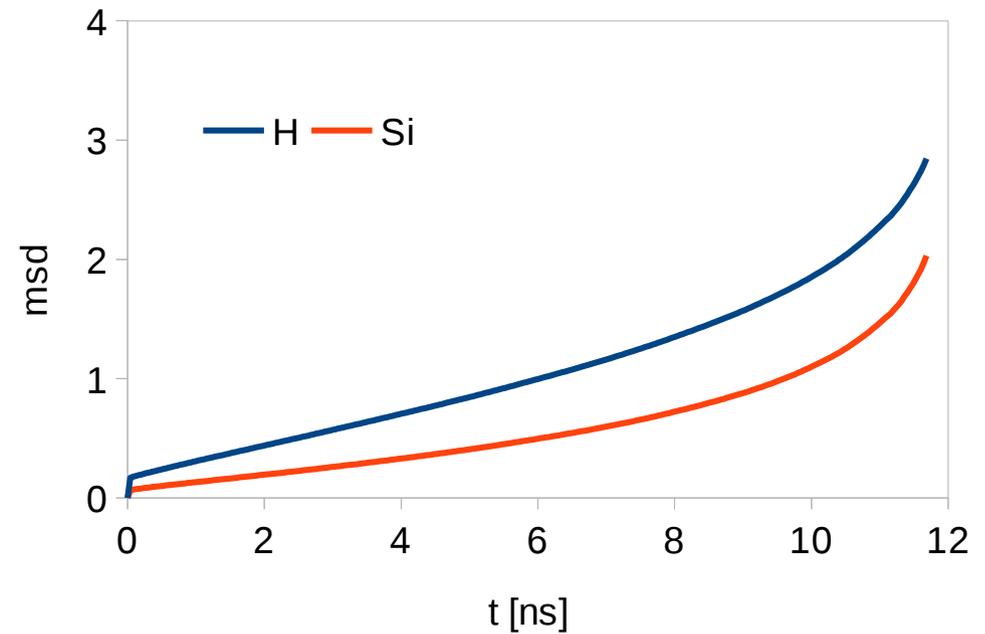
■ Diffusion and Mean Square Displacement:

msd of film with DR=5%



DR = 5 %

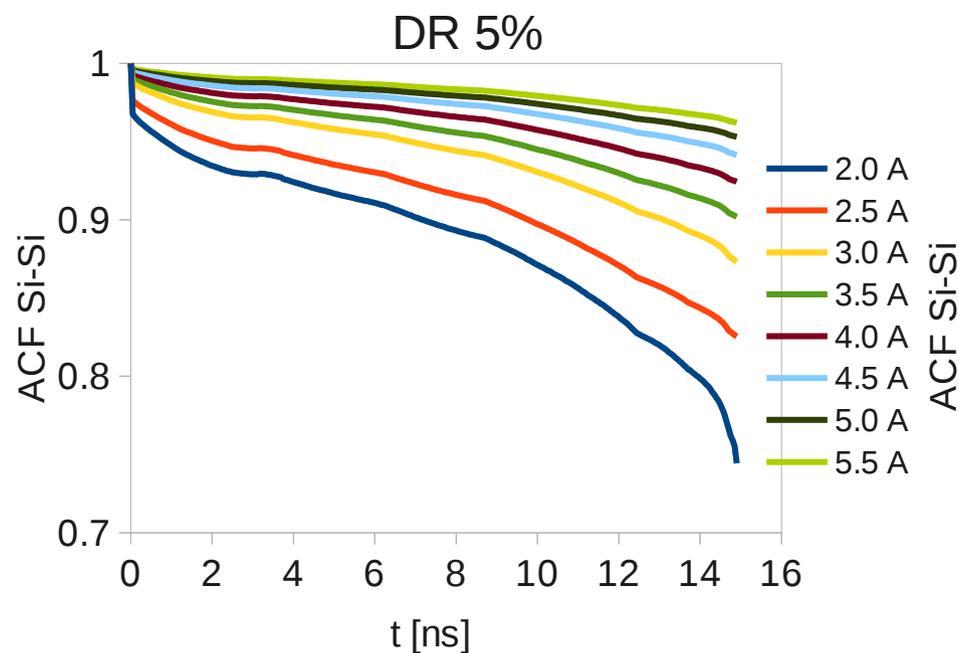
msd of film with DR=6%



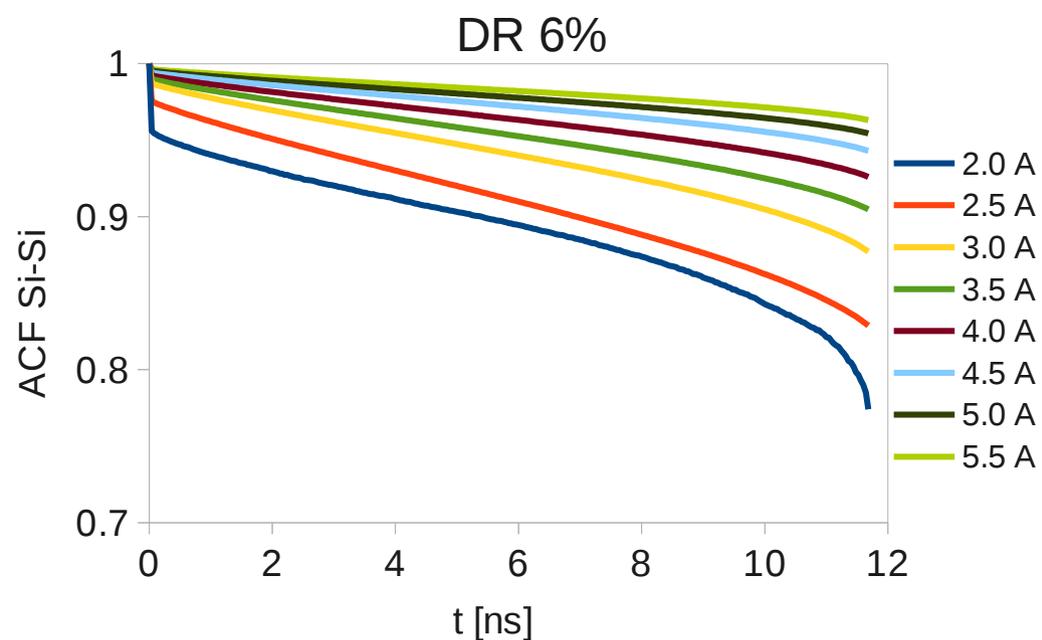
DR = 6 %

LAMMPS MD Results:

■ Autocorrelation functions:



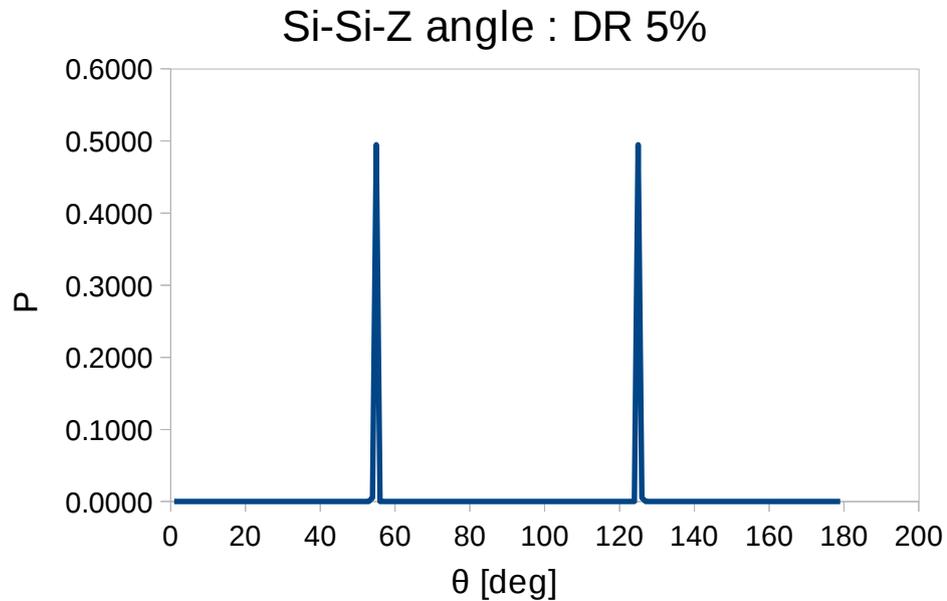
DR = 5 %



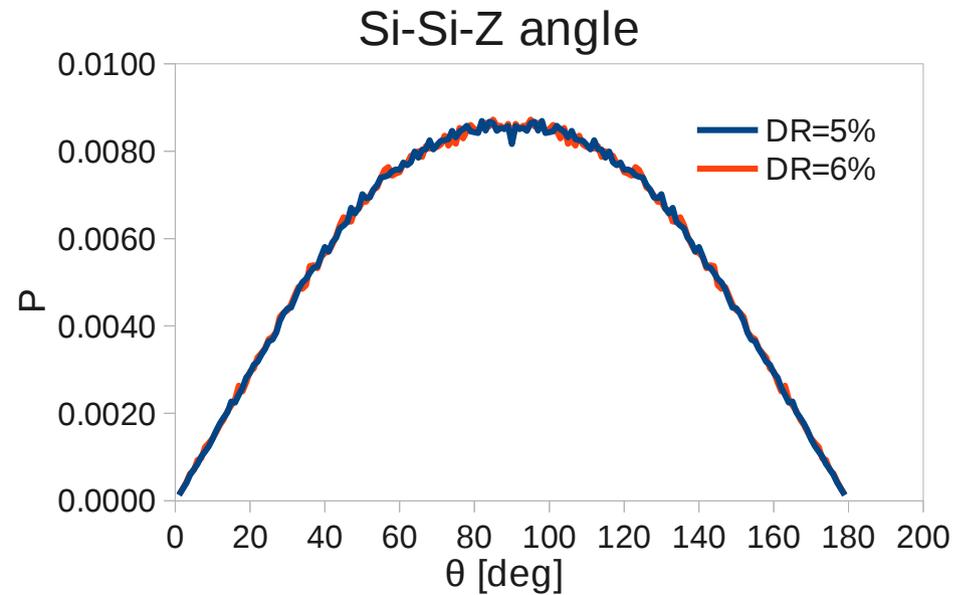
DR = 6 %

LAMMPS MD Results:

■ Bond Angle Distribution:



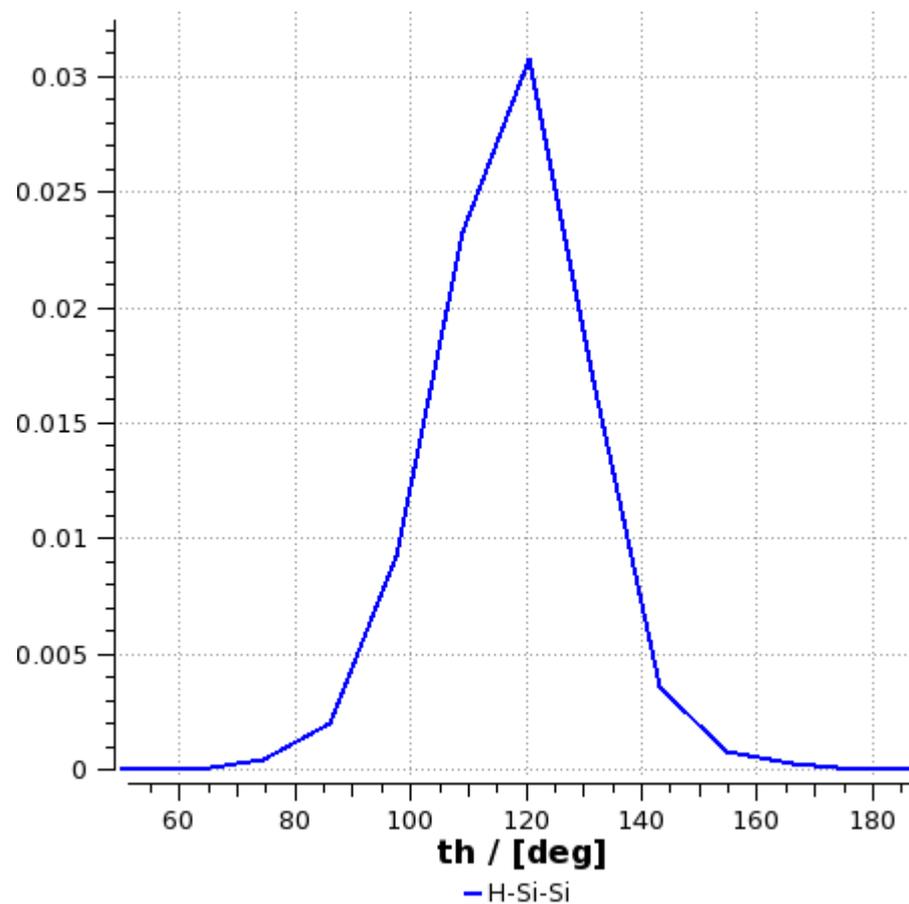
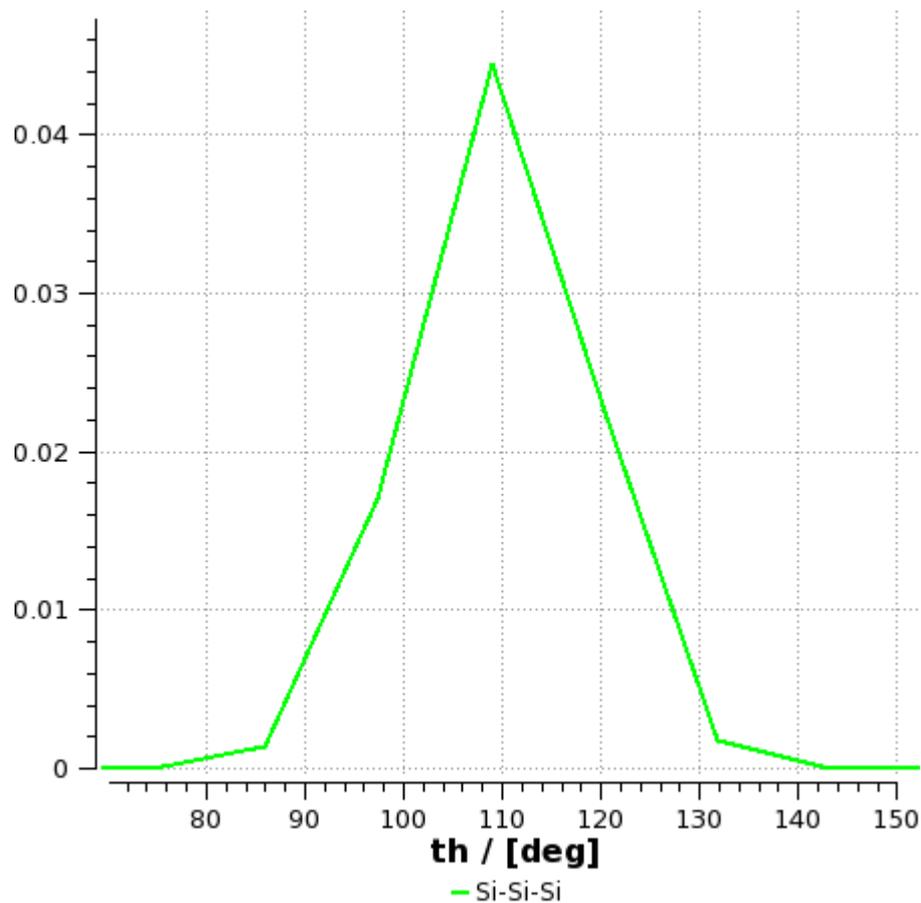
After MC



After MD

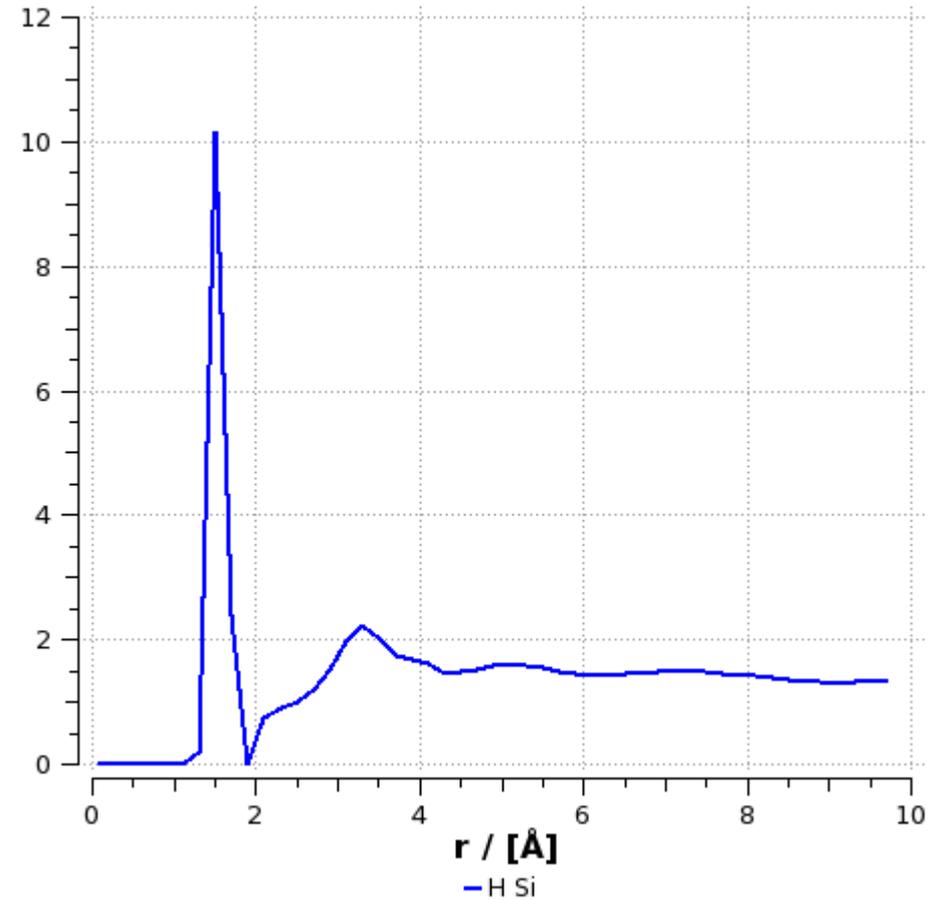
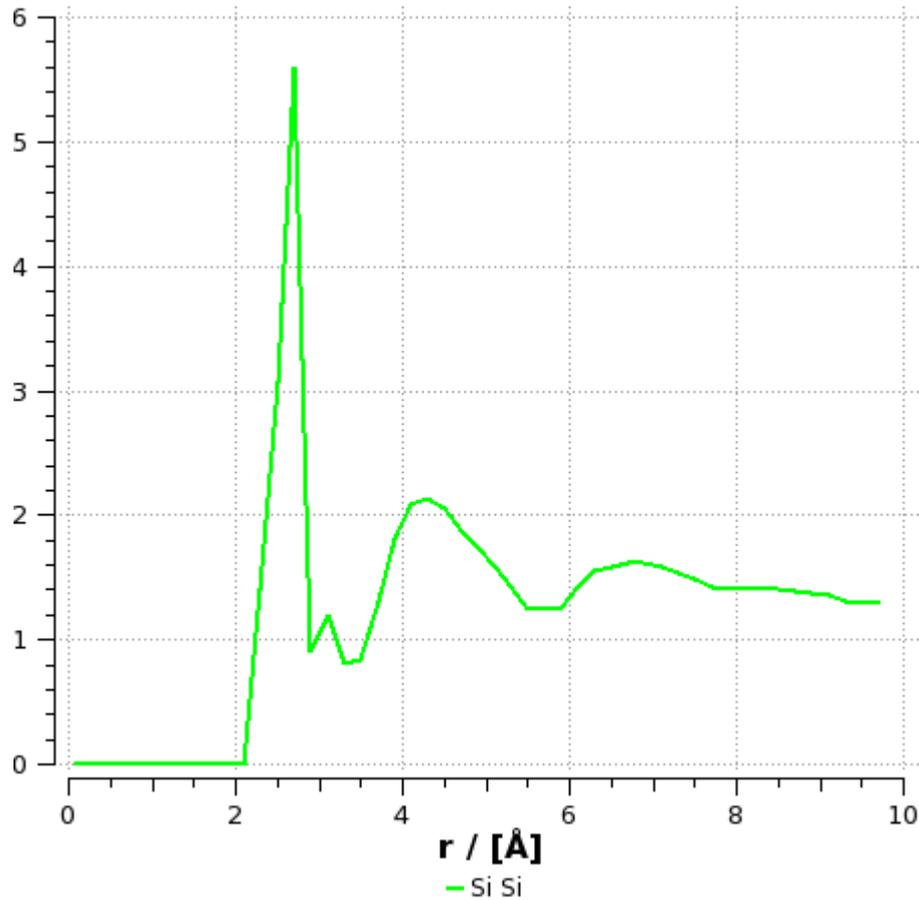
LAMMPS MD Results:

■ Bond Angle Distribution:



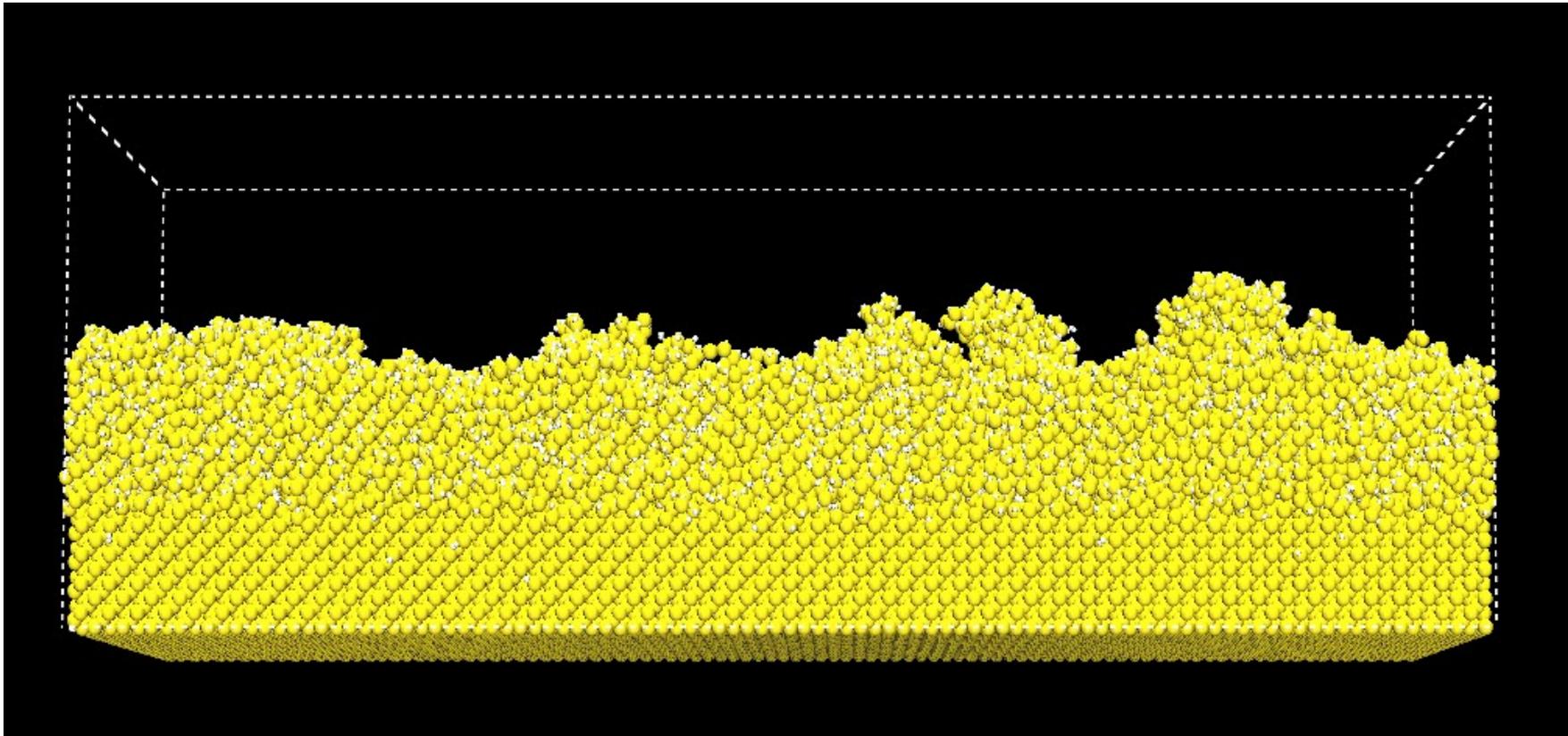
LAMMPS MD Results:

■ Pair Correlation functions:



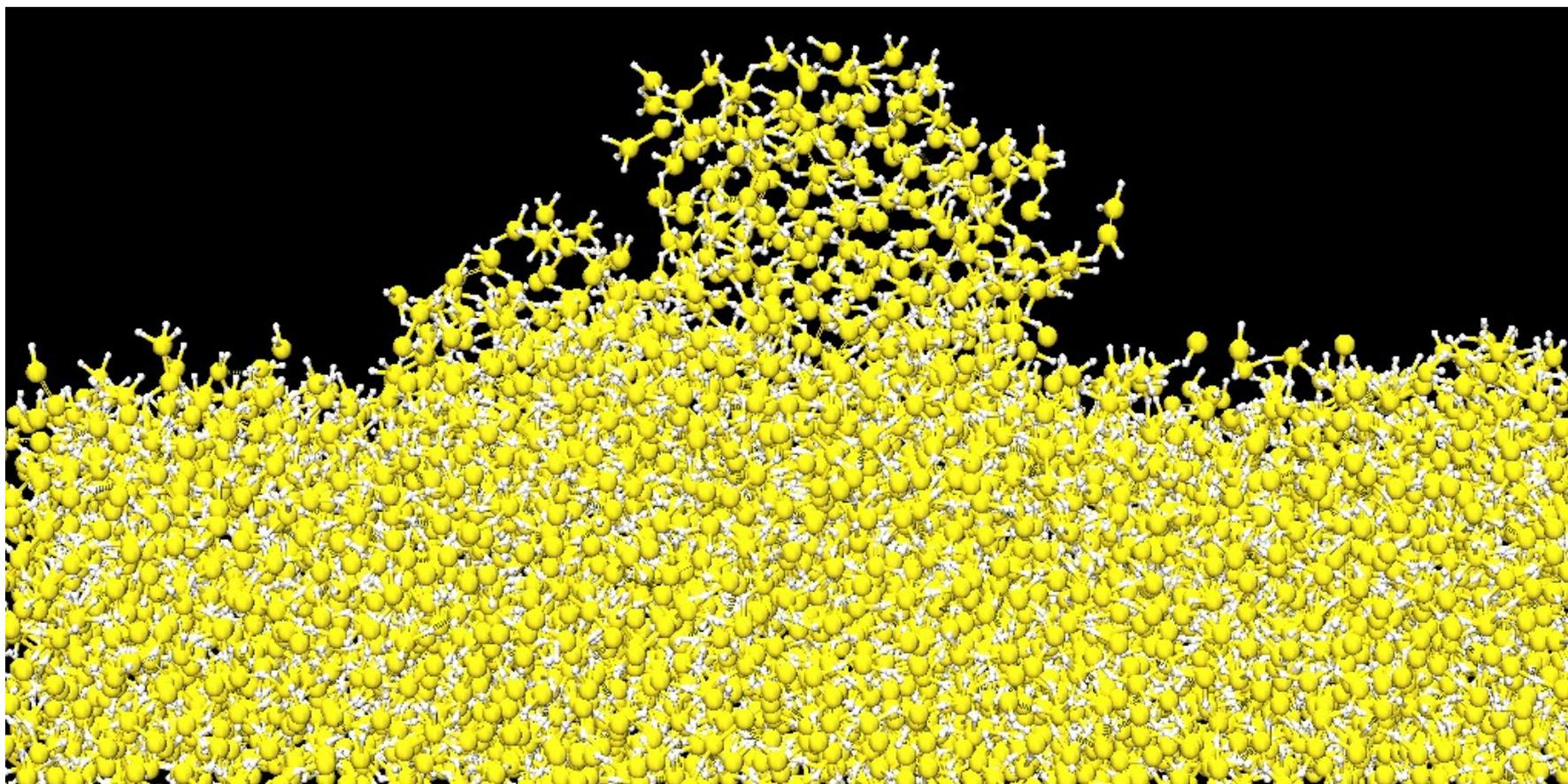
LAMMPS MD Results:

- **Structure on substrate visualized in MAPS after MD relaxation**



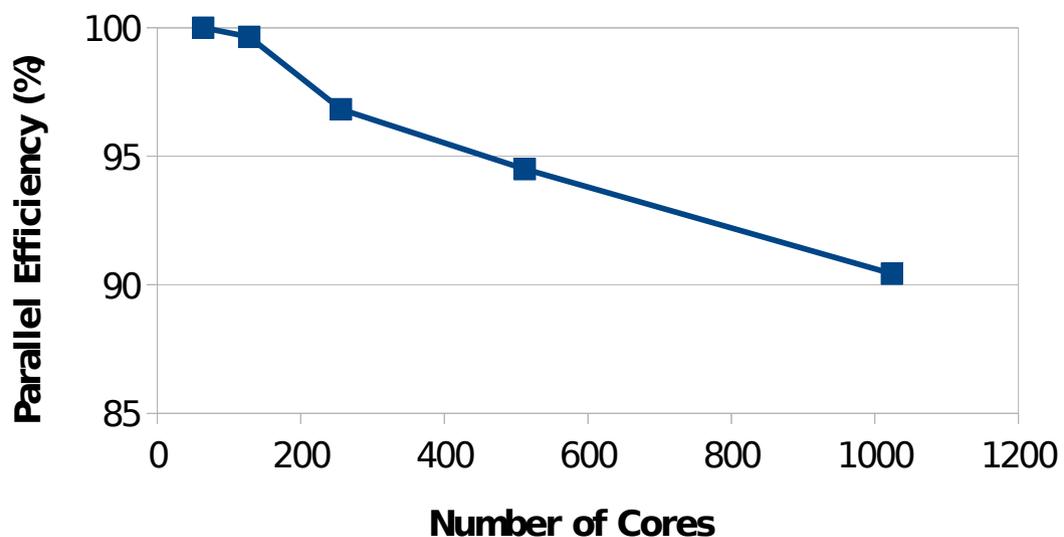
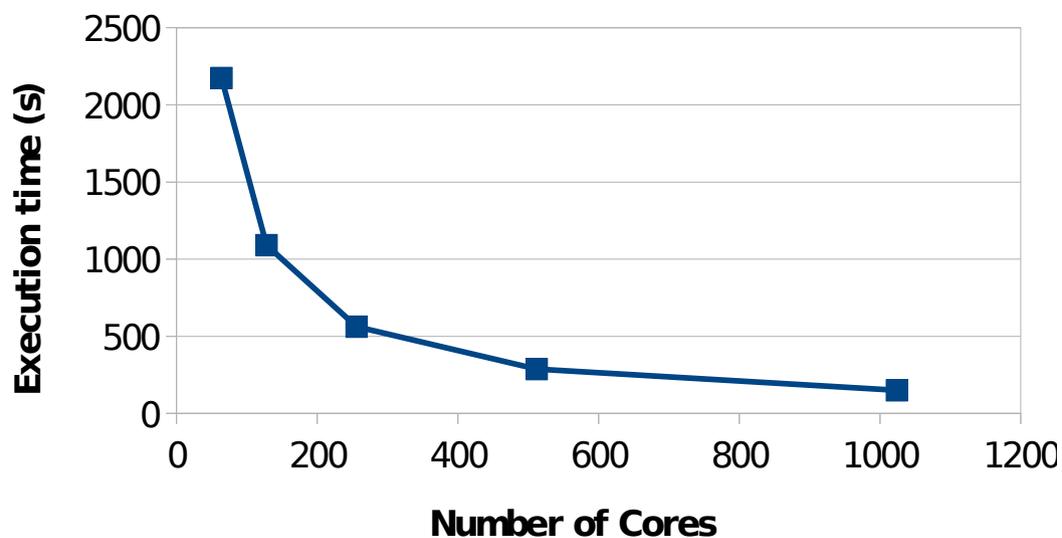
LAMMPS MD Results:

- Local Growth Zone in some detail

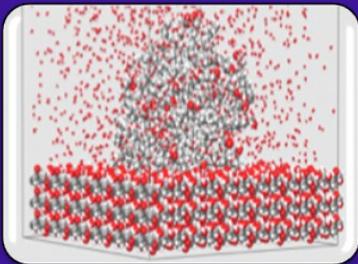


LAMMPS MD Performance with modified Tersoff potential:

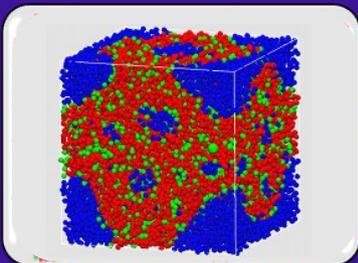
- Execution time over 10000 MD steps
- System size 965902 atoms, 80000 fixed NVT with PBC in x and y



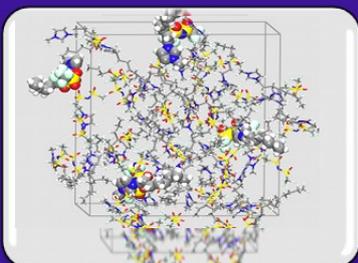
Classical Engines & Tools in MAPS



LAMMPS: A comprehensive package for molecular dynamics and mechanics simulations of periodic and non periodic systems

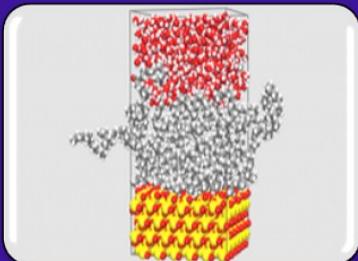


LAMMPS-DPD: Perform Dissipative Particle Dynamics simulations to study the mesoscopic behavior of fluids and related materials

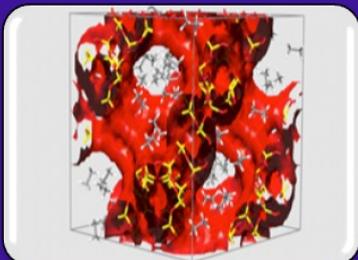


NAMD: A molecular dynamics and mechanics simulations package for studying dynamic phenomena and bulk properties of large molecular systems

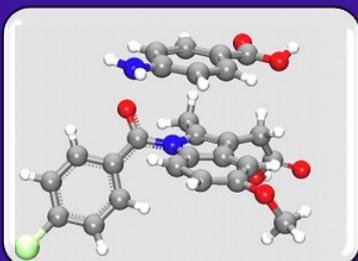
Monte Carlo based Tools



Amorphous Builder: State-of-the-art Monte Carlo based technology for building realistic models of amorphous and nano-structured materials



Towhee: A comprehensive package for Monte Carlo simulations of periodic materials in various ensembles



FHMixing: A Monte Carlo based simulation engine for the rapid estimation of thermodynamic properties of binary mixtures

Scienomics LAMMPS additions

- Tersoff with repulsive three body interactions (tersoff/rep) - will be committed soon
- Bond angle: fourier, fourier/simple, quartic
- Dihedral: quadratic, nharmonic
- Improper: fourier

Conclusions

- **Silicon films growth by PECVD modeled using KMC combined with MD**
- **With KMC:**
 - overcome the problem of multiple time scales of the reactions involved in the process
 - good qualitative prediction of the deposition rate for a range of conditions
 - good qualitative prediction of the final composition in H for a range of conditions
 - Film thickness of several 10 nm simulated
- **With the MD simulations we target:**
 - Relaxation of the films produced from KMC
 - Gradual relaxation of the film as it is developed from KMC
 - Study the molecular mechanisms relevant to properties such as crystallinity and surface roughness



**Thank you for your
attention**

Contact:

Andreas.Bick@scienomics.com

Visit: www.scienomics.com

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